

DOCKET: FI9-97-288

PATENT

#9/a
2/17/00**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

INVENTOR: C. Obszarny) EXAMINER: P. Kim
SERIAL NO.: 09/16,395 ^{2L 2/11/00}) ART UNIT: 2851
FILING DATE: 16 July 1998) DATE: 9 February 2000

FOR: APPARATUS AND METHOD FOR IN-SITU ADJUSTMENT OF
LIGHT TRANSMISSION IN A PHOTOLITHOGRAPHY PROCESS

AMENDMENT

Assistant Commissioner of Patents
Washington, DC 20231

Dear Sir:

Responsive to the Office Action mailed 10 November 1999, please amend the application as follows:

In the Specification

On page 13, line 10, after "photo mask" add the following phrase: - - with polarizing

SOG - -.

On page 13, line 18, after "photo mask" delete the reference "26".

On page 13, line 18, after "polarized sections" add the reference - - 26 - -.

On page 13, line 26, after "photo mask" add the following phrase: - - with polarizing

SOG - -.

On page 14, line 3, after "photo mask" add the following phrase: - - with polarizing

SOG - -.